

INTERNATIONAL
TECHNOLOGY ROADMAP
FOR
SEMICONDUCTORS
2006 UPDATE

TEST AND TEST EQUIPMENT

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TEST AND TEST EQUIPMENT

SUMMARY

The 2006 update to the ITRS Test Chapter is focused on minor corrections to previously published trend information. Corrections occurred to the Multi-Site wafer probing table where the parallelism for low performance microcontrollers was reduced. The Multi-Site efficiency numbers for the long-term years 2014 thru 2020 were omitted in the 2005 roadmap and have been included in the 2006 tables. NAND wafer and packaged unit test parallelism roadmap has been pulled in by 2 years and the NAND roadmap has been updated to reflect a higher bus performance starting in 2010. The system-on-chip (SOC) roadmap reflects a push out of some defect models and analog test standards as progress in these areas have not kept up with the previous forecast. The mixed signal bandwidth and sampling rate roadmaps have been pulled in by a couple of years. This update does not identify any fundamental changes to the industry roadmap.

The 2005 roadmap did not contain the definitions of high, medium, or low “performance” for the various device types included in the tables. For the 2006 update, low end logic devices have fewer than 150 signal pins and an I/O bit rate of less than 400 Mbps. High performance Flash has an I/O bit rate of greater than 125 Mbps. The definition of performance is not static and should change over the duration of this roadmap. A table for high, medium, and low end performance will be further included in 2007 roadmap.

2007 international technology working group (ITWG) activities are focused on refining the full 2005 chapter rewrite and fleshing out areas that were not fully addressed. The rapid adoption of system-in-package (SIP), SOC, and NAND devices has been driving some trends faster than expected, which has resolved some difficult challenges but created others that will require new methodology such as testing SIP die “hidden” by other die.

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Table 22 Summary of Key Test Drivers, Challenges, and Opportunities

<i>KEY DRIVERS (NOT IN ANY PARTICULAR ORDER)</i>	
Device trends	<ul style="list-style-type: none"> Increasing device interface bandwidth (both number of signals and signal data rates) Increasing device integration (SOC, SIP, MCP, 3D packaging) Integration of emerging and non-digital CMOS technologies (RF, Analog, Optical, MEMs) Package form factor and electrical / mechanical characteristics Device characteristics beyond one sided deterministic stimulus/response model
Increasing test process complexity	<ul style="list-style-type: none"> Increased device customization and line item complexity during the test process Increasing “distributed test” to maintain cost scaling Increased data feedback for tuning manufacturing Higher order dimensionality of test conditions (e.g., adding multi-power, multi-voltage, multi-freq topologies to single valued T, V, freq)
Continued economic scaling of test	<ul style="list-style-type: none"> Physical limits of further test parallelism Managing (logic) test data volume Effective limit for speed difference of HVM ATE versus DUT Acceptable increases for interface hardware and (test) socket costs Trade-off between the cost of test and the cost of quality
<i>DIFFICULT CHALLENGES (IN ORDER OF PRIORITY)</i>	
Test for yield learning	<ul style="list-style-type: none"> Critically essential for fab process and device learning below optical device dimensions
Screening for reliability	<ul style="list-style-type: none"> Increasing implementation challenges and efficacies of burn-in, IDDQ, and Vstress Erratic, non deterministic, and intermittent device behavior
Increasing systemic defects	<ul style="list-style-type: none"> Testing for local non-uniformities, not just hard defects Detecting symptoms and effects of line width variations, finite dopant distributions, systemic process defects
Potential yield losses	<ul style="list-style-type: none"> Tester inaccuracies (timing, voltage, current, temperature control, etc) Overtesting (e.g., delay faults on non-functional paths) Mechanical damage during the testing process Defects occurring in test-only circuitry, e.g., BIST Some IDDQ-only failures Faulty repairs of normally repairable circuits Overly aggressive statistical post-processing
<i>FUTURE OPPORTUNITIES (NOT IN ANY ORDER)</i>	
Test program automation (not ATPG)	Automation of generation entire test programs for ATEs
Simulation and modeling	Simulation and modeling of test interface hardware and instrumentation seamlessly integrated to the device design process
Convergence of test and system reliability solutions	Re-use and fungability of solutions between test (DFT), device, and system reliability (error detection, reporting, correction)

ATE—automatic test equipment ATPG—automatic test pattern generation BIST—built-in self test HVM—high volume manufacturing
MCP—multi-chip packaging MEMs—micro-electromechanical systems

Table 23a Multi-site Wafer Test (Package Test) for Product Segments—Near-term Years *UPDATED*

Year of Production		2005	2006	2007	2008	2009	2010	2011	2012	2013	
DRAM ½ Pitch (nm)		80	70	65	57	50	45	40	36	32	
MPU/ASIC ½ Pitch (nm)		90	78	68	59	52	45	40	36	32	
<i>High Performance ASIC/MPU</i>											
IS	Wafer test	Number of sites	8	8	8	16	16	16	16	32	32
		Multi-site efficiency [%]	95%	95%	95%	98%	98%	98%	98%	98%	98%
IS	Package test	Number of sites	4	4	4	8	8	8	8	16	16
		Multi-site efficiency [%]	92%	92%	92%	95%	95%	95%	95%	95%	95%
<i>Low Performance Microcontroller</i>											
IS	Wafer test	Number of sites	16	16	32	64	64	64	64	64	64
IS	Wafer test	Multi-site efficiency [%]	90%	90%	95%	95%	95%	95%	95%	95%	95%
IS	Package test	Number of sites	8	16	32	64	64	64	64	64	64
IS	Package test	Multi-site efficiency [%]	85%	90%	95%	95%	95%	95%	95%	95%	95%
<i>Mixed-signal</i>											
	Wafer test	Number of sites	4	4	4	8	8	16	16	16	16
IS		Multi-site efficiency [%]	85%	85%	85%	90%	90%	95%	95%	95%	95%
	Package test	Number of sites	4	8	8	16	16	16	16	16	64
IS		Multi-site efficiency [%]	85%	90%	90%	95%	95%	95%	95%	95%	95%
<i>Commodity DRAM Memory</i>											
	Wafer test	Number of sites	128	256	512	512	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer
IS		Multi-site efficiency [%]	75%	85%	90%	90%	90%	95%	95%	95%	95%
	Package test	Number of sites	128	256	256	512	512	1024	1024	1024	1024
IS		Multi-site efficiency [%]	90%	95%	95%	95%	95%	95%	95%	95%	95%
<i>Commodity Flash Memory</i>											
ADD	Wafer test	Number of sites	512	512	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer	1024 / Full wafer	2048 / Wafer scale	2048 / Wafer scale
ADD	-	Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%	95%	95%
ADD	Package test	Number of sites	128	256	256	512	512	1024	1024	1024	1024
ADD	-	Multi-site efficiency [%]	90%	92%	95%	95%	95%	95%	95%	95%	95%
<i>RF</i>											
	Wafer test	Number of sites	2	2	4	4	8	8	16	16	16
		Multi-site efficiency [%]	75%	75%	85%	85%	90%	90%	95%	95%	95%
	Package test	Number of sites	4	4	8	16	32	48	64	64	64
		Multi-site efficiency [%]	75%	90%	92%	95%	97%	97%	97%	97%	97%

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Table 23b Multi-site Wafer Test (Package Test) for Product Segments—Long-term Years **UPDATED**

Year of Production		2014	2015	2016	2017	2018	2019	2020	
DRAM ½ Pitch (nm)		28	25	22	20	18	16	14	
MPU/ASIC ½ Pitch (nm)		28	25	22	20	18	16	14	
High Performance ASIC/MPU									
IS	Wafer test	Number of sites	32	64	64	128	256	256	512 / Wafer scale
		Multi-site efficiency [%]	98%	98%	98%	98%	98%	98%	98%
IS	Package test	Number of sites	16	32	32	64	128	128	128
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
Low Performance Microcontroller									
IS	Wafer test	Number of sites	64	128	128	128	128	128	128
IS	Wafer test	Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
IS	Package test	Number of sites	64	128	128	128	128	128	128
IS	Package test	Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
Mixed-signal									
IS	Wafer test	Number of sites	16	32	32	64	128	128	256
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
IS	Package test	Number of sites	64	128	128	256	256	256	512
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
Commodity DRAM Memory									
IS	Wafer test	Number of sites	1024 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
IS	Package test	Number of sites	1024	2048	2048	2048	2048	2048	2048
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
Commodity Flash Memory									
ADD	Wafer test	Number of sites	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	2048 / Wafer scale	
ADD	-	Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	
ADD	Package test	Number of sites	1024	2048	2048	2048	2048	2048	
ADD	-	Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	
RF									
IS	Wafer test	Number of sites	32	32	32	64	128	128	256
		Multi-site efficiency [%]	95%	95%	95%	95%	95%	95%	95%
IS	Package test	Number of sites	128	128	128	256	256	256	512
		Multi-site efficiency [%]	97%	97%	97%	97%	97%	97%	97%

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

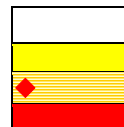


Table 24 SOC Model

			130 nm	90 nm	65 nm
Transistor Count (Million)	High Frequency Logic Part	Logic	4.7	7.1	10.9
		Memory	8.6	19.5	42.3
	Low Frequency Logic Part	Logic	6.8	10.3	15.7
		Memory	19.6	42.5	89.9
	Total		39.7	79.4	158.9

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Table 25a System on Chip Test Requirements—Near-term Years **UPDATED**

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	35	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	85	76	67	60	54	48	42	38	34
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
<i>Embedded Cores</i>									
IS Standardization of Core Test Data [1]	Standard format on EDA/ATE			Extension to Analog Cores					
<i>Embedded Cores: Logic</i>									
IS Test Logic Insertion at RTL Design	Partially		Partially	Fully					
IS Testability Analysis and Overhead Estimation at RTL Design	Ad hoc	Partially used	Partially used	Fully					
BISR for Logic Cores	Minimal	Some						Logic BISR	
<i>Embedded Cores: Logic - Random Pattern Logic BIST</i>									
Area Investment beyond Scan (%) [2]	3.1	3.1	3.1	3.1	3.1	3.1	3.1	3.1	3.1
<i>Embedded Cores: Logic - Compressed Deterministic Pattern Test</i>									
Area Investment beyond Scan (%) [3]	1.1	1.2	1.3	1.4	1.5	1.6	1.6	1.7	1.8
Test Pattern Length (Number of Captures) [4]	1.0	1.3	1.6	2.0	2.5	3.2	4	5	6
Test Pattern Length Compression Ratio [5]	1.0	1.4	2.0	3.1	5.2	9.2	18	23	30
Test Data Volume Compression Ratio [6]	100	120	150	210	300	460	770	860	980
<i>Embedded Cores: Memory</i>									
IS Area Investment of SRAM BIST/BISR (Kgates/Mbits)	35	35	35	35	35	35	35	35	35
Repairing Mechanism of Embedded SRAM Cells [7]	BISR		BISR for Row & Col R/D				BISR for More Sophisticated R/D		
<i>Embedded Cores: Analog</i>									
DFT (BIST, BOST) for Analog Cores	Limited use (PLL, ADC, etc.)				Partial				
Design for Failure Analysis of Analog Cores	Ad hoc								
<i>Core Access</i>									
Use of Standard Interface on IP Core Access	Partially								
Analog-Mixed Signal Core Access	Direct Access				Analog wrapper [8]			Standard analog wrapper [8]	
<i>SoC Level Testing</i>									
Test Strategy for IP Core-Based Design [9]	Partially automated			Fully automated					
DFT Selection for Cores	DFT selection for cores			Selection for cores/fully automated EDA tool					
IS DFT at Higher Level Design [10]	No			Partially	Partially	Partially	Yes	Yes	Yes
<i>Fault Model for SoC</i>									
IS Test quality model for SoC Level defect Coverage [11]	fault models for each core			New method, its coverage [12]					
Delay Fault Model with High Accuracy	Partially	Partially	Fully usable						
IS X-talk Fault Model	No			No	Partially	Fully usable			
<i>Manufacturing</i>									
IS Diagnosis Interface/Data [13]	Standard format and methods on IP core			Standard format and methods on IP core	Automated SoC diagnosis				

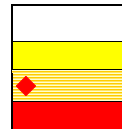
BOST—built off-chip self test

BISR—built-in self repair

Table 25b System on Chip Test Requirements—Long-term Years *UPDATED*

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	30	27	24	21	19	17	15
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
<i>Embedded Cores</i>							
IS Standardization of Core Test Data [1]	Extension to Analog Cores						
<i>Embedded Cores: Logic</i>							
IS Test Logic Insertion at RTL Design	Fully						
IS Testability Analysis and Overhead Estimation at RTL Design	Fully						
BISR for Logic Cores	Logic BISR						
<i>Embedded Cores: Logic - Random Pattern Logic BIST</i>							
Area Investment beyond Scan (%) [2]	3.1	3.1	3.1	3.1	3.1	3.1	3.1
<i>Embedded Cores: Logic - Compressed Deterministic Pattern Test</i>							
Area Investment beyond Scan (%) [3]	1.9	2	2.1	2.1	2.1	2.1	2.1
Test Pattern Length (Number of Captures) [4]	8	10	13	16	20	25	32
Test Pattern Length Compression Ratio [5]	40	55	68	83	100	130	160
Test Data Volume Compression Ratio [6]	1,140	1,360	1,450	1,560	1,680	1,810	1,960
<i>Embedded Cores: Memory</i>							
IS Area Investment of SRAM BISR/BISR (K gates/Mbits)	35	35	35	35	35	35	35
Repairing Mechanism of Embedded SRAM Cells [7]	BISR for More Sophisticated R/D						
<i>Embedded Cores: Analog</i>							
DFT (BIST, BOST) for Analog Cores	Partial				Full use		
Design for Failure Analysis of Analog Cores	Partially structural	Structural					
<i>Core Access</i>							
Use of Standard Interface on IP Core Access	Partially	Fully					
Analog-Mixed Signal Core Access	Standard analog wrapper [8]						
<i>SoC Level Testing</i>							
Test Strategy for IP Core-Based Design [9]	Fully automated						
DFT Selection for Cores	Selection for cores/fully automated EDA tool						
IS DFT at Higher Level Design [10]	Yes						
<i>Fault Model for SoC</i>							
IS Test quality model for SoC Level defect Coverage [11]	New method, its coverage [12]						
Delay Fault Model with High Accuracy	Fully usable						
IS X-talk Fault Model	Fully usable						
<i>Manufacturing</i>							
IS Diagnosis Interface/Data [13]	Automated SoC diagnosis						

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known



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Definitions for Tables 25a and b:

[1] The standardization of test data format needs to reduce turn-around-time of test program development

[2] Area investment of random pattern logic BIST consists of BIST controller and test points.

[3] Area investment of compressed deterministic pattern test logic consists of controller and test points.

[4] Required number of test pattern length (number of captures), which is normalized based on the number on 2005.

[5] Test pattern compression ratios are values which are necessary to suppress the total test pattern length (sum of those for stuck-at, transition, path delay and X-talk tests) in the table within the required test pattern length.

[6] Ratio of compressed test data volume in the tester memory against conventional scan test data volume with same fault coverage

[7] Hard repair which uses optical or electrical fuse devices for the programming

[8] Extended wrapper structure to access to embedded analog-MS cores, not chip-level analog boundary-scan

[9] The strategy contains test control integration, test scheduling for low power consumption, test time and test pin reduction

IS [10] High-level synthesis with testability analysis for scan or Instruction-based test

IS [11] The standard menu of fault models and coverage is required to popularize IP Cores

[12] A method to obtain overall test quality measure of SoC considering all embedded devices; logic, memory and analog.

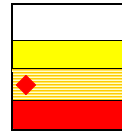
IS [13] The standardization of diagnosis data format and interface (Independent of DFT and ATE) is required to reduce turn-around-time of failure analysis

Table 26a Logic Test Requirements—Near-term Years

<i>Year of Production</i>	2005	2006	2007	2008	2009	2010	2011	2012	2013	
<i>DRAM ½ Pitch (nm) (contacted)</i>	80	70	65	57	50	45	40	36	32	
<i>MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)</i>	90	78	68	59	52	45	40	36	32	
<i>MPU Physical Gate Length (nm)</i>	32	28	25	22	20	18	16	14	13	
<i>Part 1: High Volume Microprocessor Trends Drivers</i>										
Functions per chip at production (million transistors [Mtransistors])	193	193	386	386	386	773	773	773	1,546	
Chip size at production (mm ²)	111	88	140	111	88	140	111	88	140	
Number of processor cores	2	2	4	4	4	8	8	8	16	
Nominal V _{dd} Range (V)	0.9–1.1	0.9–1.1	0.8–1.1	0.8–1.0	0.8–1.0	0.7–1.0	0.7–1.0	0.7–0.9	0.6–0.9	
Chip-to-board (off-chip) speed (high-performance, for peripheral buses) (MHz)	3125	3906	4883	6103	7629	9536	TBD	14901	18626	
<i>Part 2: High Volume Microprocessor Test Requirements</i>										
I/O data rate (GT/s)	0.1 - 3	0.1 - 6	0.1 - 6	0.1 - 6	0.2 - 12	0.2 - 12	0.2 - 12	0.2 - 15	0.2 - 15	
I/O types	Slow speed scan / DFT, source synchronous, clock forwarding, clock embedded				Slow speed scan / DFT, clock forwarded, clock embedded					
Total device maximum power consumption at test (W)	Client	200	200	200	200	300	300	300	300	300
	Server	200	250	300	300	300	300	300	300	300
Number of power supplies per site	1–4	1–4	1–6	1–6	1–6	1–4	1–4	1–3	1–3	
Power supplies voltage range (V)	0.7–2.0	0.7–2.0	0.6–2.0	0.6–2.0	0.6–2.0	0.6–12	0.6–12	0.6–12	0.6–12	
Scan vector memory (Mbit per pin)	64-256	64-256	64-256	64-256	64-512	64-512	64-512	64-512	64-1024	
Functional vector memory (M-vectors per pin)	16-128	16-128	16-128	16-128	16-256	16-256	16-256	16-256	16-512	

Values for the year 2011 will be determined in the 2006 ITRS Update.

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known



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Table 26b Logic Test Requirements—Long-term Years

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
<i>Part 1: High Volume Microprocessor Trends Drivers</i>							
Functions per chip at production (million transistors [Mtransistors])	1,546	1,546	3,092	3,092	3,092	6,184	6,184
Chip size at production (mm ²)	111	88	140	111	88	140	111
Number of processor cores	16	16	32	32	32	64	64
Nominal Vdd Range (V)	0.6–0.9	0.6–0.8	0.5–0.8	0.5–0.7	0.5–0.7	0.4–0.7	0.4–0.6
Chip-to-board (off-chip) speed (high-performance, for peripheral buses) (MHz)	TBD	29103	36379	TBD	56843	TBD	TBD
<i>Part 2: High Volume Microprocessor Test Requirements</i>							
I/O data rate (GT/s)	0.2-20	0.2-20	0.2-20	0.2-40	0.2-40	0.2-40	0.2-40
I/O types	Slow speed scan / DFT, advanced clock embedded, optical						
Total device maximum power consumption at test (W)	Client	300	300	300	300	300	300
	Server	400	400	400	400	400	400
Number of power supplies per site	1–3	1–3	1–3	1–3	1–3	1–3	1–3
Power supplies voltage range (V)	0.6–12	0.6–12	0.6–48	0.6–48	0.6–48	0.6–48	0.6–48
Scan vector memory (Mbit per pin)	64–1024	64–1024	64–1024	64–1024	64–1024	64–1024	64–1024
Functional vector memory (M-vectors per pin)	16–512	16–512	16–512	16–1024	16–1024	16–1024	16–1024

Values for the years 2014, 2017, 2019, and 2020 will be determined in the 2006 ITRS Update.

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

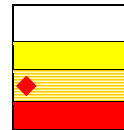


Table 27a Commodity DRAM Test Requirements—Near-term Years **UPDATED**

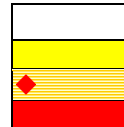
Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
DRAM Capacity (Gbits)									
R&D	8	8	16	16	16	32	32	32	64
Mass production	1	2	2	2	4	4	4	8	8
DRAM data rate (Gbs)	0.67	0.80	1.00	1.20	1.20	1.33	1.33	1.50	1.50
Performance DRAM data rate (Gbs)	1.8	2.25	2.5	3	3.5	5	5	6	6
DRAM bit width/device (mass production)	16	16	16	16	16	16	16	16	16
Device CLK rate (GHz)	0.3	0.3	0.4	0.5	0.5	0.6	0.7	0.7	0.8
IS Overall timing accuracy (ps)	40	40	32	32	25	25	25	CBD	

CLK—clock signal **CBD**—cannot be determined

Table 27b Commodity DRAM Test Requirements—Long-term Years **UPDATED**

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
DRAM Capacity (Gbits)							
R&D	64	64	128	128	128	256	256
Mass production	8	16	16	16	32	32	32
DRAM data rate (Gbs)	1.8	1.8	2.0	2.0	2.25	2.25	2.5
Performance DRAM data rate (Gbs)	8	8	10	10	12	12	14
DRAM bit width/device (mass production)	16	16	16	16	16	16	16
Device CLK rate (GHz)	0.9	0.9	1.0	1.1	1.1	1.2	1.3
IS Overall timing accuracy (ps)	CBD						

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known



12 Test and Test Equipment

Table 28a Commodity Flash Memory Test Requirements—Near-term Years **UPDATED**

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
<i>NAND Device Characteristics</i>									
<i>Capacity (Gbits)</i>									
R&D	32	32	64	64	128	128	128	256	256
Mass production	8	8	16	16	32	32	32	64	64
Data width (bits)	16	16	16	16	16	16	16	16	16
<i>Power Supplies</i>									
Power supply voltage range	1.5–5.5	1.5–5.5	1.5–5.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5
Power supplies per device	2	2	2	2	2	2	2	2	2
Maximum current (MA)	35	35	35	35	35	35	35	35	35
<i>Pattern Generator</i>									
Tester channels per device	24	24	24	24	24	24	24	24	24
<i>Timing</i>									
IS Maximum I/O data rate (Mbs)	40	40	50	50	50	66	66	100	100
IS Accuracy OTA (ns)	1.2	1.2	1	1	1	0.8	0.8	0.5	0.5
<i>NOR Device Characteristics</i>									
<i>Capacity (Gbits)</i>									
R&D	4	4	8	8	16	16	16	32	32
Mass production	1	1	2	2	4	4	4	8	8
Data width (bits)	16	16	16	32	32	32	32	32	32
Power supply voltage range	1.0–5.5	1.0–5.5	1.0–5.5	1.0–5.5	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3
Power supplies per device***	2	2	2	2	2	2	2	2	2
Maximum current (MA)	150	150	150	150	150	150	150	150	150
Tester channels per test site	64	72	72	72	72	72	72	72	72
Maximum I/O data rate (Mbs)	166	200	200	200	266	266	266	333	333
Accuracy OTA (ns)	0.3	0.2	0.2	0.2	0.18	0.18	0.18	0.15	0.15

OTA—overall ATE timing accuracy

*** Discrete only

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

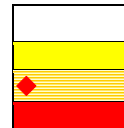
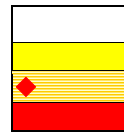


Table 28b Commodity Flash Memory Test Requirements—Long-term Years **UPDATED**

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
<i>NAND Device Characteristics</i>							
<i>Capacity (Gbits)</i>							
R&D	256	512	512	512	1024	1024	1024
Mass production	64	128	128	128	256	256	256
Data width (bits)	16	16	16	16	16	16	16
<i>Power Supplies</i>							
Power supply voltage range	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5	1.5–3.5
Power supplies per device	2	2	2	2	2	2	2
Maximum current (MA)	35	35	35	35	35	35	35
<i>Pattern Generator</i>							
Tester channels per device	24	24	24	24	24	24	24
<i>Timing</i>							
IS Maximum I/O data rate (Mbs)	<u>100</u>	<u>100</u>	<u>133</u>	<u>133</u>	<u>133</u>	<u>133</u>	<u>133</u>
IS Accuracy OTA (ns)	<u>0.5</u>	<u>0.5</u>	<u>0.4</u>	<u>0.4</u>	<u>0.4</u>	<u>0.4</u>	<u>0.4</u>
<i>NOR Device Characteristics</i>							
<i>Capacity (Gbits)</i>							
R&D	32	64	64	64	128	128	128
Mass production	8	16	16	16	32	32	32
Data width (bits)	32	32	32	32	32	32	32
Power supply voltage range	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3	0.9–3.3
Power supplies per device***	2	2	2	2	2	2	2
Maximum current (MA)	150	150	150	150	150	150	150
Tester channels per test site	72	72	72	72	72	72	72
Maximum I/O data rate (Mbs)	333	400	400	400	400	400	400
Accuracy OTA (ns)	0.15	0.12	0.12	0.12	0.12	0.12	0.12

*** Discrete only

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known



14 Test and Test Equipment

Table 29a Embedded Memory (DRAM and Flash) Test Requirements—Near-term Years

<i>Year of Production</i>	2005	2006	2007	2008	2009	2010	2011	2012	2013	
<i>DRAM ½ Pitch (nm) (contacted)</i>	80	70	65	57	50	45	40	36	32	
<i>MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)</i>	90	78	68	59	52	45	40	36	32	
<i>Embedded DRAM</i>										
Embedded DRAM size (Mbits) *										
R&D	256	512	512	512	1024	1024	1024	2048	2048	
Mass production	128	256	256	256	512	512	512	1024	1024	
Failure concerns	Particle defects; array noise, data retention					Particle defects, array noise, sense-amp imbalance				
Wafer level test	Single and double insertion					In-line defect detection				
Usage of on-chip test	100% BIST/BISR					100% BIST/100% BISR				
<i>Embedded Flash</i>										
Embedded flash size (Mbits) *										
R&D	64	128	128	128	256	256	256	512	512	
Mass production	32	64	64	64	128	128	128	256	256	
Embedded mixed memory size (Mbits) *										
Flash	32	64	64	64	128	128	128	256	256	
DRAM	32	64	64	64	128	128	128	256	256	
Failure concerns	Oxide defects; ONO scaling; over-erase					Sense-amp imbalance				
Wafer level test	Single and double insertion					In-line defect detection				
Usage of on-chip test	BIST/BIST/DAT					BIST/BISR				

DAT—direct access DFT

Number of bits in mass production is approximately 50% of number of bits in R&D

* Solution space is both on-chip and stacked die

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

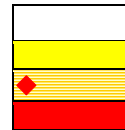


Table 29b Embedded Memory (DRAM and Flash) Test Requirements—Long-term Years

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
Embedded DRAM							
<i>Embedded DRAM size (Mbits)</i>							
R&D	2048	4096	4096	4096	8184	8192	8192
Mass production	1024	2048	2048	2048	4092	4096	4096
Failure concerns	Particle defects, array noise, sense-amp imbalance						
Wafer level test	In-line defect detection						
Usage of on-chip test	100% BIST/100% BISR						
Embedded Flash							
<i>Embedded flash size (Mbits)</i>							
R&D	512	1024	1024	1024	2046	2048	2048
Mass production	256	512	512	512	1023	1024	1024
<i>Embedded mixed memory size (Mbits)</i>							
Flash	256	512	512	512	1023	1024	1024
DRAM	256	512	512	512	1023	1024	1024
Failure concerns	Sense-amp imbalance						
Wafer level test	In-line defect detection						
Usage of on-chip test	BIST/BISR						

* Solution space is both on-chip and stacked die

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

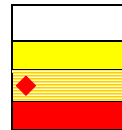


Table 30a Mixed-signal Test Requirements—Near-term Years **UPDATED**

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013	2014	
DRAM 1/2 Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32	28	
MPU/ASIC Metal 1 (M1) 1/2 Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32	90	
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13	11	
<i>Low Frequency Waveform</i>											
BW (MHz)	50	50	50	75	75	75	100	100	100	100	
Sample rate (MS/s)	Moving from Nyquist sample rates to over/under sampling sources/digitizers										
Resolution (bits)	DSP computation to 24 bits – however effective number of bits will be limited by noise floor										
Noise floor (dB/RT Hz)	-155	-155	-155	-160	-160	-160	-165	-165	-165	-165	
<i>Very High Frequency Waveform Source</i>											
Level V (pk-pk)	4	4	4	4	Driven by communication physical layer standards – likely to be lower						
Accuracy (±)	0.50%	0.50%	0.50%	0.50%	Likely to remain the same						
IS BW (MHz)	1500	1500	1600	1900	2250	2700	2700	3000	3000	3000	
IS Sample rate (MS/s)	6000	6000	6400	7600	9000	10,800	10,800	12000	12000	12000	
IS Resolution (bits) AWG/Sine†	8/10	8/10	8/10	8/10	8/10	8/10	8/10	10/12	10/12	10/12	
IS Noise floor (dB/RT Hz)	-135	-135	-140	-140	-140	-140	-140	-145	-145	-145	
<i>Very High Frequency Waveform Digitizer</i>											
Level V (pk-pk)	4	4	4	4	Driven by communication physical layer standards – likely to be lower						
Accuracy (±)	0.50%	0.50%	0.50%	0.50%	Likely to remain the same						
BW (MHz) (undersampled)	6400	8000	9200	10800	10800	12500	12500	15000	15000	15000	
Sample rate (MS/s)	Direct conversion <400 MS/s							Direct conversion <600 MS/s			
Resolution (bits)	Minimum 12 bits – noise floor is more important							Minimum 14 bits – noise floor is more important			
Noise floor (dB/RT Hz)	-145	-145	-145	-145	-145	-145	-145	-150	-150	-150	
<i>Time Measurement</i>											
Jitter measurement (ps RMS)	Will be driven by high-speed serial communication ports										
Frequency measurement (MHz)	Will be driven by high-performance ASIC clock rates										
Single shot time capability (ps)	Will be driven by high-speed serial communication ports										
RF/Microwave instrumentation	Same as RF test requirements – see this new section										
<i>Special Digital Capabilities</i>											
D/A and A/D digital data rate (MB/s)	Same as high performance ASIC “off-chip data rate”										
Sample clock jitter (ps RMS)	<0.2	<0.2	<0.2	<0.1	<0.1	<0.1	<0.1	<0.1	<0.1	<0.1	

AWG—array waveguide gratings BW—bandwidth pk-pk—peak to peak

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known

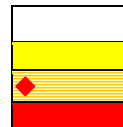
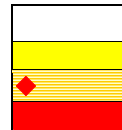


Table 30b Mixed-signal Test Requirements—Long-term Years **UPDATED**

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
<i>Low Frequency Waveform</i>							
BW (MHz)	100	100	100	100	100	100	100
Sample rate (MS/s)	Moving from Nyquist sample rates to over/under sampling sources/digitizers						
Resolution (bits)	DSP computation to 24 bits – however effective number of bits will be limited by noise floor						
Noise floor (dB/RT Hz)	-165	-165	-165	-165	-165	-165	-165
<i>Very High Frequency Waveform Source</i>							
Level V (pk-pk)	Driven by communication physical layer standards – likely to be lower						
Accuracy (±)	Likely to remain the same						
IS BW (MHz)	3750	3750	3750	3750	3750	3750	3750
IS Sample rate (MS/s)	15000	15000	15000	15000	15000	15000	15000
IS Resolution (bits) AWG/Sine†	10/12	10/12	10/12	10/12	10/12	10/12	10/12
Noise floor (dB/RT Hz)	-145	-145	-145	-145	-145	-144	-143
<i>Very High Frequency Waveform Digitizer</i>							
Level V (pk-pk)	Driven by communication physical layer standards – likely to be lower						
Accuracy (±)	Likely to remain the same						
BW (MHz) (undersampled)	15000	15000	15000	15000	15000	15000	15000
Sample rate (MS/s)	Direct conversion <600 MS/s						
Resolution (bits)	Minimum 14 bits – noise floor is more important						
Noise floor (dB/RT Hz)	-150	-150	-150	-150	-150	-150	-150
<i>Time Measurement</i>							
Jitter measurement (ps RMS)	Will be driven by high-speed serial communication ports						
Frequency measurement (MHz)	Will be driven by high-performance ASIC clock rates						
Single shot time capability (ps)	Will be driven by high-speed serial communication ports						
RF/Microwave instrumentation	Same as RF test requirements – see this new section						
<i>Special Digital Capabilities</i>							
D/A and A/D digital data rate (MB/s)	Same as high performance ASIC “off-chip data rate”						
Sample clock jitter (ps RMS)	<0.1	<0.1	<0.1	<0.1	<0.1	<0.1	<0.1

Manufacturable solutions exist, and are being optimized
 Manufacturable solutions are known
 Interim solutions are known
 Manufacturable solutions are NOT known



Definitions for Mixed-signal Test Requirements Table 30:

Low Frequency Source and Digitizer—This is the basic, minimum, instrument set of any mixed-signal tester. Telecommunications, advanced audio and wireless baseband will drive these specifications. Differential inputs/outputs are required.
Very High Frequency Waveform Source—Disk storage applications will drive sample rate and bandwidth. Local area network devices will drive sample rate, resolution and amplitude accuracy. Differential outputs are required.
Very High Frequency Waveform Digitizer—Undersampled (down conversion, track-and-hold, etc) bandwidth is shown. The sample rates and bit resolutions are for a direct conversion digitizer, which is usually preceded by the undersampler. Storage and network devices will drive digitizer specifications. Differential inputs are required.
Special Digital Capabilities—For converter testing, the ability to source a digital signal to a D/A and capture a digital signal from an A/D.

18 Test and Test Equipment

Table 31a Burn-in Requirements—Near-term Years

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
Clock input frequency (MHz)	400	400	400	400	400	400	400	400	400
Off-chip data frequency (MHz)	75	75	75	75	75	75	75	75	75
Power dissipation (W per DUT)	600	600	600	600	600	600	600	600	600
<i>Power Supply Voltage Range (V)</i>									
High-performance ASIC / microprocessor / graphics processor	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5
Low-end microcontroller	0.7–10.0	0.7–10.0	0.7–10.0	0.7–10.0	0.7–10.0	0.5–10	0.5–10	0.5–10	0.5–10
Mixed-signal	0.5–500	0.5–500	0.5–500	0.5–500	0.5–500	0.5–500	0.5–500	0.5–500	0.5–500
<i>Maximum Number of Signal I/O</i>									
High-performance ASIC	384	384	384	384	384	384	384	384	384
High-performance microprocessor / graphics processor / mixed-signal	128	128	128	128	128	128	128	128	128
Commodity memory	72	72	72	72	72	72	72	72	72
<i>Maximum Current (A)</i>									
High-performance microprocessor	400	450	450	450	450	450	450	450	450
High-performance graphics processor	40	80	100	150	200	200	200	200	200
Mixed-signal	20	20	20	20	20	30	30	30	30
<i>Burn-in Socket</i>									
Pin count	2500	3000	3000	3000	3000	3000	3000	3000	3000
Pitch (mm)	0.4	0.4	0.3	0.3	0.3	0.2	0.2	0.2	0.2
Power consumption (A/Pin)	2.0	3.0	3.0	4.0	4.0	5.0	5.0	5.0	5.0
<i>Wafer Level Burn-In</i>									
Maximum burn-in temperature (°C)	150±3	150±3	175±3	175±3	175±3	175±3	175±3	175±3	175±3
<i>Pad Layout – Linear</i>									
Minimum pad pitch (µm)	80	80	65	65	65	65	65	65	65
Minimum pad size (µm)	60	60	50	50	50	50	50	50	50
Maximum number of probes	70k	70k	70k	70k	70k	70k	70k	70k	70k
<i>Pad Layout – Periphery, Area Array</i>									
Minimum pad pitch (µm) *1	100	100	100	80	80	80	80	80	80
Minimum pad size (µm)	45	40	40	35	35	35	35	30	30
Maximum number of probes	125k	125k	150k	150k	150k	150k	150k	150k	150k
Power consumption (W/DUT – Low-end microcontroller, DFT/BIST SOC *2)	10	10	10	10	10	20	20	20	20
Vector memory depth (M vectors – DFT/BIST SOC *2)	16	32	32	64	64	64	64	64	64

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

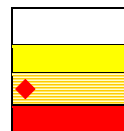


Table 31b Burn-in Requirements—Long-term Years

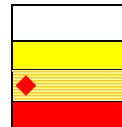
<i>Year of Production</i>	2014	2015	2016	2017	2018	2019	2020
<i>DRAM ½ Pitch (nm) (contacted)</i>	28	25	22	20	18	16	14
<i>MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)</i>	28	25	22	20	18	16	14
<i>MPU Physical Gate Length (nm)</i>	11	10	9	8	7	6	6
<i>Clock input frequency (MHz)</i>	400	400	400	400	400	400	400
<i>Off-chip data frequency (MHz)</i>	75	75	75	75	75	75	75
<i>Power dissipation (W per DUT)</i>	600	600	600	600	600	600	600
<i>Power Supply Voltage Range (V)</i>							
High-performance ASIC / microprocessor / graphics processor	0.5–2.5	0.5–2.5	0.5–2.5	0.5–2.5	0.4–2.5	0.4–2.5	0.4–2.5
Low-end microcontroller	0.5–10	0.5–10	0.5–10	0.5–10	0.5–10	0.5–10	0.5–10
Mixed-signal	0.5–500	0.5–1000	0.5–1000	0.5–1000	0.5–1000	0.5–1000	0.5–1000
<i>Maximum Number of Signal I/O</i>							
High-performance ASIC	384	384	384	384	384	384	384
High-performance microprocessor / graphics processor / mixed-signal	128	128	128	128	128	128	128
Commodity memory	72	72	72	72	72	72	72
<i>Maximum Current (A)</i>							
High-performance microprocessor	450	450	450	450	450	450	450
High-performance graphics processor	200	200	200	200	200	200	200
Mixed-signal	30	30	30	30	30	30	30
<i>Burn-in Socket</i>							
Pin count	3000	3000	3000	3000	3000	3000	3000
Pitch (mm)	0.2	0.1	0.1	0.1	0.08	0.08	0.08
Power consumption (A/Pin)	5.0	5.0	6.0	6.0	6.0	6.0	6.0
<i>Wafer Level Burn-In</i>							
Maximum burn-in temperature (°C)	175±3	175±3	175±3	175±3	175±3	175±3	175±3
<i>Pad Layout - Linear</i>							
Minimum pad pitch (µm)	65	50	50	50	50	50	50
Minimum pad size (µm)	50	40	40	40	40	40	40
Maximum number of probes	70k	140k	140k	140k	140k	140k	140k
<i>Pad Layout – Periphery, Area Array</i>							
Minimum pad pitch (µm) *1	80	60	60	60	60	60	60
Minimum pad size (µm)	30	25	25	25	25	25	25
Maximum number of probes	150k	300k	300k	300k	300k	300k	300k
Power consumption (W/DUT – low-end microcontroller, DFT/BIST SOC *2)	20	20	20	20	20	20	20
Vector memory depth (M vectors – DFT/BIST SOC *2)	64	128	128	128	256	256	256

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known



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Table 32a Handler (Memory—Pick and Place) Requirements—Near-term Years **UPDATED**

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
Parallel testing	64–128	128–256	128–256	128–256	128–256	128–256	128–256	128–512	128–512
ADD Parallel testing – FLASH	128	256	256	512	512	1024	1024	1024	1024
Index time (S)	3–5	3–5	2–5	2–5	2–4	2–4	2–4	2–4	2–4
Throughput (devices per hour)	8–10K	8–10K	8–10K	8–12K	8–12K	12–20K	12–20K	12–20K	12–20K
Sorting	5–9	5–9	5–9	5–9	5–9	5–9	5–9	5–9	5–9
Temperature set point range (°C)	-55 to 155	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175
Temperature accuracy (°C)	±2	±2	±2	±2	±1.5	±1.5	±1.5	±1.5	±1.5
Number of pins/device	40–250	40–250		6–400	40–400	6–400	40–400	6–400	6–400
Pin pitch (mm)	0.5–1.0	0.4–1.0	0.4–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0
Ball edge to package edge clearance (mm)	0	0	0	0	0	0	0	0	0
Minimum package thickness (mm)	0.3–1.8	0.3–1.8	0.3–1.8	0.2–1.8	0.2–1.8	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)
Conversion time (minutes)	40	1 (kitless)	1 (kitless)	1 (kitless)	1 (kitless)	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM

GEM—generic equipment model

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

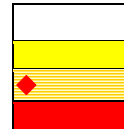
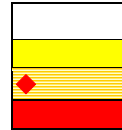


Table 32b Handler (Memory—Pick and Place) Requirements—Long-term Years *UPDATED*

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
Parallel testing	128 - 512	128–512	128–512	128 - 512	128–512	128 - 512	128–512
ADD Parallel testing – FLASH	1024	2048	2048	2048	2048	2048	2048
Index time (S)	2–4	2–4	2–4	2–4	2–4	2–4	2–4
Throughput (devices per hour)	12–20K	12–20K	12–20K	12–20K	12–20K	12–20K	12–20K
Sorting	5–9	5–9	5–9	5–9	5–9	5–9	5–9
Temperature set point range (°C)	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175
Temperature accuracy (°C)	±1.5	±1.5	±1.5	±1.5	±1.5	±1.5	±1.5
Number of pins/device	6–400	6–400	6–400	6–400	6–400	6–400	6–400
Pin pitch (mm)	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0	0.3–1.0
Ball edge to package edge clearance (mm)	0	0	0	0	0	0	0
Minimum package thickness (mm)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)	0.2–1.8 (kitless)
Conversion time (minutes)	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM	1 (kitless) GEM– HSEM

Manufacturable solutions exist, and are being optimized
Manufacturable solutions are known
Interim solutions are known
Manufacturable solutions are NOT known



Notes for Tables 32a and b:

Index time was done from test end signal reception from tester to the test start signal transmission of handler.

Units per hour (UPH) calculated with zero-second test time and no lot-size generated interruptions.

Sort is number of stackable JEDEC tray sleeves used for output of devices.

± assumes a normal distribution centered at the temperature with 3 standard deviations equal to the ± number.

Allowable temperature rise due to a step power pulse of the corresponding power density.

Asynchronous capability is defined as the capability of the handler to input, socket and output devices independently with multiple test sites-no gang socketing.

Uninterrupted tray flow requires the handler operation to not be halted when loading/unloading trays.

Auto-Retest requires units to be retested automatically without the need for operator intervention. This is different from a simple reprobe in that the part must be socketed on a different change kit head (if possible).

Electromigration interference (EMI) event field is a measurement of electric emissions due to electrostatic discharge (ESD) events during normal handler operation.

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Table 33a Handler (Logic—Pick and Place) Requirements—Near-term Years

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
Parallel testing < 10 sec test time	8	16	16	16	16	32	16	32	64
Parallel testing > 10 sec test time	16	32	32	32	32	64	64	128	128
Index time (S)	0.3–0.4	0.3–0.4	0.25–0.3	0.25–0.3	0.25	0.25	0.25	0.25	0.25
Throughput (devices per hour)	8–12K	8–12K	9–14K	9–14K	12–20K	12–20K	12–20K	12–20K	12–20K
Sorting	3–6	3–6	3–6	3–6	3–6	3–6	3–6	3–6	3–6
Temperature set point range (°C)	-55 to 155	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175
Tj accuracy at start of test (°C)	± 0.5	± 2	± 2	± 2	± 2	± 2	± 2	± 2	± 2
Total thermal load (Watts) – MPU	125	125	150	150	175	200	200	200	200
Thermal Watt density (Watts/cm ²) – MPU	130	130	175	175	200	225	225	225	225
Maximum socket load per unit (kg)	24	27	50	50	35	60	35	60	60
Asynchronous capability	Yes	Yes	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Number of pins or lands/device	750	750	800	800	850	850	850	850	850
Pin/land pitch (mm)	1.1	1.1	0.3	0.3	0.8	0.3	0.3	0.3	0.2
Conversion time (minutes)	30	30	15	15	15	5	5	5	5
Uninterrupted tray loading/auto-2A	No	Yes	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Reliability (hours)	400	600	800	1000	1000	1000	1000	1200	1200

Table 33b Handler (Logic—Pick and Place) Requirements—Long-term Years

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
Parallel testing < 10 sec test time	64	64	64	64	64	64	64
Parallel testing > 10 sec test time	128	128	128	128	256	256	256
Index time (S)	0.25	0.25	0.25	0.25	0.25	0.25	0.25
Throughput (devices per hour)	12–20K	20–28K	20–28K	20–28K	20–28K	20–28K	20–28K
Sorting	3–6	3–6	3–6	3–6	3–6	3–6	3–6
Temperature set point range (°C)	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175	-55 to 175
Tj accuracy at start of test (°C)	± 2	± 2	± 2	± 2	± 2	± 2	± 2
Total thermal load (Watts) – MPU	200	250	250	250	300	300	300
Thermal Watt density (Watts/cm ²) – MPU	225	250	250	250	250	250	250
Maximum socket load per unit (kg)	60	65	65	65	75	75	75
Asynchronous capability	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Number of pins or lands/device	850	900	900	900	1000	1000	1000
Pin/land pitch (mm)	0.3	0.2	0.2	0.3	0.2	0.2	0.2
Conversion time (minutes)	5	5	5	5	5	5	5
Uninterrupted tray loading/auto-2A	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Reliability (hours)	1000	1200	1400	1400	1400	1400	1400

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

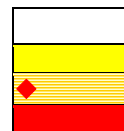


Table 34a Handler (Network and Communications—Pick and Place)—Near-term Years

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm) (contacted)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
Parallel testing	4	8	8	8	8	8	16	16	16
Index time (S)	0.3–0.4	0.3–0.4	0.3–0.4	0.3–0.4	0.25–0.3	0.25–0.3	0.25	0.25	0.25
Throughput (devices per hour)	4–6K	8–12K	8–12K	8–12K	9–14K	9–14K	12–20K	12–20K	12–20K
Sorting	3–6	3–6	3–6	3–6	3–6	3–6	3–6	3–6	3–6
Set point range (°C)	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150
Temperature accuracy (°C)	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5
Allowable device temperature rise (°C)	20	20	20	20	20	20	20	20	20
Maximum socket load per unit (kg)	16	20	24	27	30	30	35	35	35
Asynchronous capability	No	No	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Number of pins or lands/device	700	700	750	750	800	800	850	850	850
Pin/land pitch (mm)	1.2	1.2	1.1	1.1	1	1	0.8	0.6	0.6
Conversion time (minutes)	30	30	30	30	15	15	15	5	5
Uninterrupted tray loading/auto-2A	No	No	No	Yes	Yes	Yes	Yes	Yes	Yes
Reliability (hours)	80	100	100	168	168	500	500	1000	1000

Table 34b Handler (Network and Communications—Pick and Place)—Long-term Years

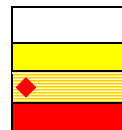
Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm) (contacted)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
Parallel testing	16	16	16	32	32	32	32
Index time (S)	0.25	0.25	0.25	0.25	0.25	0.25	0.25
Throughput (devices per hour)	12–20K	12–20K	12–20K	20–28K	20–28K	20–28K	20–28K
Sorting	3–6	3–6	3–6	3–6	3–6	3–6	3–6
Set point range (°C)	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150	-45 to +150
Temperature accuracy (°C)	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5	-0.5
Allowable device temperature rise (°C)	20	20	20	20	20	20	20
Maximum socket load per unit (kg)	35	35	35	35	35	35	35
Asynchronous capability	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Number of pins or lands/device	850	850	850	900	900	900	1000
Pin/land pitch (mm)	0.6	0.6	0.6	0.4	0.4	0.4	0.4
Conversion time (minutes)	5	5	5	5	5	5	5
Uninterrupted tray loading/auto-2A	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Reliability (hours)	1000	1000	1000	1000	1000	1000	1000

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known



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Table 35a Prober (Logic MPU—Pick and Place) Requirements—Near-term Years

Year of Production	2005	2006	2007	2008	2009	2010	2011	2012	2013
DRAM ½ Pitch (nm)	80	70	65	57	50	45	40	36	32
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	90	78	68	59	52	45	40	36	32
MPU Printed Gate Length (nm)	45	40	35	32	28	25	22	20	18
MPU Physical Gate Length (nm)	32	28	25	22	20	18	16	14	13
Wafer diameter (mm)	300	300	300	300	300	300	300	300	300
Pad pitch	Peripheral (mm)	40–100	40–100	40–100	30–80	30–80	30–60	30–60	30–60
	Bump (mm)	30	30	30	30	30	20	20	20
Wafer thickness (mm)	80–775	80–775	80–775	80–775	80–775	50–1000	50–1000	50–1000	50–1000
Maximum I/O pads	3000	3000	3000	4000	4000	5300	5300	5300	5300
Chuck positioning accuracy	X & Y (µm)	4	4	4	2	2	2	2	2
	Z (µm)	2	2	1	1	1	0.5	0.5	0.5
Probe-to-pad alignment (µm)	4.5	4.5	4.5	4.5	4.5	3.5	3.5	3.5	3.5
Maximum chuck force (kg)	50	100	100	100	100	100	100	100	100
Parallel testing	16	32	32	32	32	64	64	64	128
Set point range (°C)	-30 to +85	-30 to +85	-30 to +85	-30 to +85	-30 to +85	-45 to +125	-45 to +125	-45 to +125	-45 to +125
Total power (Watts)	150	150	200	200	250	250	250	250	250
Power density (Watt/cm ²)	90	90	90	90	120	120	120	120	120

Table 35b Prober (Logic MPU—Pick and Place) Requirements—Long-term Years

Year of Production	2014	2015	2016	2017	2018	2019	2020
DRAM ½ Pitch (nm)	28	25	22	20	18	16	14
MPU/ASIC Metal 1 (M1) ½ Pitch (nm)(contacted)	28	25	22	20	18	16	14
MPU Printed Gate Length (nm)	16	14	13	11	10		
MPU Physical Gate Length (nm)	11	10	9	8	7	6	6
Wafer diameter (mm)	450	450	450	450	450	450	450
Pad pitch	Peripheral (mm)	30–60	30–60	30–60	30–60	30–60	3–60
	Bump (mm)	20	20	20	20	20	20
Wafer thickness (mm)	50–1000	50–1000	50–1000	50–1000	50–1000	50–1000	50–1000
Maximum I/O pads	5300	5300	5300	5300	5300	5300	5300
Chuck positioning accuracy	X & Y (µm)	2	2	2	2	2	2
	Z (µm)	0.5	0.5	0.5	0.5	0.5	0.5
Probe-to-pad alignment (µm)	3.5	3.5	3.5	3.5	3.5	3.5	3.5
Maximum chuck force (kg)	100	100	100	100	100	100	100
Parallel testing	128	128	128	128	128	128	128
Set point range (°C)	-45 to +125	-45 to +125	-45 to +125	-45 to +125	-45 to +125	-45 to +125	-45 to +125
Total power (Watts)	250	300	300	250	300	300	300
Power density (Watt/cm ²)	120	120	120	120	120	120	120

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

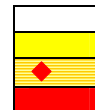


Table 36 Test Handler and Prober Difficult Challenges *UPDATED*

		CHALLENGE	ISSUE / GOAL
IS	Memory handler	Package form factors	Variety of sizes, thicknesses, and ball pitches requires kitless handlers with thin-die handling capability
		Ball-to-package edge gap	As this decreases from 0.6 mm to 0 mm, new handling and socketing methods must be introduced
		Massive parallelism	Parallelism at greater than x128 drives roadmap, thermal, and alignment challenges
Logic handler	Logic handler	Thermal control	Improved temperature control and temperature rise control due to high power densities during test
		Operations improvements	Continuous lot processing (lot cascading), auto-retest, asynchronous device socketing, low-conversion times
		ESD	Products more sensitive to ESD, while on-die protection circuitry increases cost.
		Packaging technology	Lower stress socketing, low-cost change kits, higher I/O count, heat lids change thermal characteristics
		Through put and multi-site	Increase in multi-site handling capability for short test time devices (1–7 seconds), thus increase in throughput
Netcom handler	Netcom handler	New packaging technologies	Known good die solutions (KGD), stacked die packaging, thin die packaging
		Temperature control	Wide range tri-temperature soak requirements (-45°C to 150°C) increases system complexity
		Operations improvements	Continuous lot processing (lot cascading), auto-retest, low conversion times, asynchronous operation
		EMI/RF up to 40 GHz	Shielding issues associated with high frequency testing (>10 GHz)
Logic prober	Logic prober	Thermal contact resistance between wafer and chuck	The high thermal resistance and variation in contact resistance across chuck are required to improve temperature control and reduce temperature rise of device under test
		Heat dissipation at elevated temperature	Heat dissipation of >100 Watts at > 85°C is a configuration gap in the prober industry
		Probe card optical standardization	With advancement in probe card technology a new optical alignment methodology must be developed

Table 37 Probe Card Difficult Challenges—Near-term Years

CHALLENGE	ISSUE / GOAL
Geometry	<p>Probe technologies to support peripheral fine pitch probe of 25 μm, peripheral staggered pad probes at effective pitches of 20/40, and fine pitch (45 μm) for dual row, non-staggered probing on all four die sides.</p> <p>Fine pitch vertical probe technologies to support 130 μm pitch area array solder bump and 50 μm pitch staggered pad devices.</p> <p>Multi-site pad probing technologies with corner pitch capability below 125 μm.</p> <p>Reduction of pad damage at probe commensurate with pad size reductions (or better).</p> <p>Alternative probe technology for 75 μm on 150 μm pitch dense array (vertical probe; bumped device).</p> <p>Increasing probe array planarity requirements in combination with increasing array size.</p>
Parallel test	<p>Need a probe technology to handle the complexity of SOC devices while probing more than one device.</p> <p>Current probe technologies have I/O limitations for bumped device probes.</p>
Probing at temperature	<p>Reduce effects on probes for non-ambient testing -40 to 150°C; especially for fine-pitch devices.</p> <p>For effects on Handlers and Probers, see that section.</p>
Product	<p>Probe technologies to direct probe on copper bond pads including various oxidation considerations.</p> <p>Probe technologies for probing over active circuitry (including flip-chip).</p>
Probe force	<p>Reduce per pin force required for good contact resistance to lower total load for high pin count and multi DUT probe applications. Evaluation and reduction of probe force requirements to eliminate die damage, including interlayer dielectric damage with low-κ dielectrics.</p>
Probe cleaning	<p>Development of high temperature (85 C–15°C) <i>in situ</i> cleaning mediums/methods, particularly for fine pitch, multi-DUT and non-traditional probes.</p> <p>Reduction of cleaning requirements while maintaining electrical performance to increase lifetime.</p>
Cost and delivery	<p>Fine pitch or high pin count probe cards are too expensive and take too long to build.</p> <p>Time and cost to repair fine pitch or high pin count probe cards is very high.</p> <p>The time between chip design completion (“tape-out”) and the availability of wafers to be probed is less than the time required to design and build a probe card in almost every probe technology except traditional cantilever.</p> <p>Space transformer lead times are too long, thus causing some vertical probe technologies to have lengthy lead-times.</p>
Probe metrology	<p>Tools are required that support fine pitch probe characterization and pad damage measurements.</p> <p>Metrology correlation is needed—repair versus on-floor usage.</p>
High power devices	<p>Probe technologies will need to incorporate thermal management features capable of handling device power dissipations approaching 1000 Watts and the higher currents (≥ 1.5 amp) flowing through individual probe points.</p>
Contact resistance	<p>Probe technologies that achieve contact resistance < 5 Ohms initially and throughout use are needed.</p>
High frequency probing	<p>Traditional probe technologies do not have the necessary electrical bandwidth for higher frequency devices. At the top end are RF devices, requiring up to 40 GHz.</p>

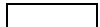



Table 38a Wafer Probe Technology Requirements—Near-term Years *UPDATED*

Year of Production	2005		2006		2007		2008		2009		2010		2011		2012		2013	
DRAM ½ Pitch (nm) (contacted)	80		70		65		57		50		45		40		36		32	
I/O Pad Size (µm)	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y
Wirebond	35	60	30	55	30	55	25	45	25	45	25	45	25	45	20	35	20	35
Bump	75	75	75	75	60	60	60	60	50	50	50	50	50	50	50	50	50	50
Scrub (% of I/O)	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH
Wirebond	25	50	25	50	25	50	20	40	20	40	20	40	20	40	20	40	20	40
Bump	30	30	30	30	30	30	30	30	30	30	30	30	30	30	30	30	30	30
<i>Multi-DUT Volume (% of Total Product Type Wafers Probed)</i>																		
Memory (DRAM)	99.9		99.9		99.9		99.9		99.9		99.9		99.9		99.9		99.9	
ASIC	50		60		75		75		75		75		75		75		75	
Microprocessor	50		60		75		75		75		75		75		75		85	
RF	45		50		50		60		60		60		60		60		60	
Mixed-signal	60		60		75		75		80		80		80		80		80	
<i>Size of Probed Area (mm²)</i>																		
Memory (DRAM)	50% of wafer		50% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer	
ADD Memory (FLASH)	50% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer	
ASIC	2050		2050		2050		2400		2400		2400		2400		2400		2400	
Microprocessor	2050		2050		2050		2400		2400		2400		2400		2400		2400	
RF	900		900		1225		1225		1225		1225		1225		1225		1225	
Mixed-signal	1413		1413		1600		1600		1600		1600		1600		1600		1600	
<i>Number of Probe Points /Touchdown</i>	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total
Memory (DRAM)	14500	18700	14500	18700	17000	20000	17000	20000	17000	20000	17000	20000	17000	20000	20000	25000	20000	25000
ASIC	1050	4000	1050	5000	1050	5000	1200	6000	1500	7500	1500	7500	1500	7500	3000	9000	3000	9000
Microprocessor	1024	10000	1024	15000	1024	20000	1024	20000	1024	20000	1024	20000	1024	20000	2000	30000	2000	30000
RF	250	450	250	450	350	630	350	630	350	630	350	630	350	630	350	630	350	630
Mixed-signal	450	600	450	600	510	680	510	680	510	680	510	680	510	680	510	680	510	680
<i>Maximum Current (mA)</i>	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage
Memory (DRAM)	100	<10	125	<10	125	<10	125	<10	125	<10	125	<10	125	<10	125	<10	125	<10
ASIC	200	<10	300	<10	400	<10	500	<10	500	<10	500	<10	500	<10	1000	<10	1000	<10
Microprocessor	800	<10	1000	<10	1200	<10	1200	<10	1500	<10	1500	<10	1500	<10	1500	<10	1500	<10

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Year of Production	2005		2006		2007		2008		2009		2010		2011		2012		2013	
DRAM ½ Pitch (nm) (contacted)	80		70		65		57		50		45		40		36		32	
RF	200	<10	225	<10	225	<10	225	<10	225	<10	225	<10	225	<10	225	<10	225	<10
Mixed-signal	250	<10	275	<10	275	<10	275	<10	275	<10	275	<10	275	<10	275	<10	275	<10
Maximum Resistance (Ohm)	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series
Memory (DRAM)	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3
ASIC	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3
Microprocessor	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2
RF	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5
Mixed-signal	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5
Chuck Set-point (°C)	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.
Memory (DRAM)	-40	140	-40	150	-40	150	-50	180	-50	180	-50	180	-50	180	-50	180	-50	180
ASIC	25	110	0	140	0	140	-10	140	-10	140	-10	140	-10	14	-10	14	-10	14
Microprocessor	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135
RF	5	120	5	120	5	120	5	120	5	120	5	120	5	120	5	120	5	120
Mixed-signal	25	125	25	125	25	125	25	125	25	125	25	125	25	125	25	125	25	125
<i>Soak Time (minutes)</i>																		
Memory (DRAM)	10		8		8		8		7		7		7		7		7	
ASIC	8		7		7		7		6		6		6		6		6	
Microprocessor	10		10		10		9		9		9		9		9		9	
RF	10		10		9		9		9		9		9		9		9	
Mixed-signal	10		10		9		9		9		9		9		9		9	
<i>Order Lead-time—Single DUT (weeks)</i>	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order
Memory (DRAM)	6	3	5.5	3	5	3	4	2	4	2	4	2	4	2	4	2	4	2
ASIC	2.5	1.5	2.5	1.5	2.5	1.5	2	1	2	1	2	1	2	1	2	1	2	1
Microprocessor	2.5	1.5	2.5	1.5	2.5	1.5	2	1	2	1	2	1	2	1	2	1	2	1
RF	4	2	3.5	1.5	3.5	1.5	3	1	3	1	3	1	3	1	3	1	3	1
Mixed-signal	3	2	2.5	1.5	2.5	1.5	2	1	2	1	2	1	2	1	2	1	2	1
<i>Order Lead-time—Multi-DUT (weeks)</i>	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order
Memory (DRAM)	7	4	6	3	5	3	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5
ASIC	5	2	4	1.5	3.5	1.5	3	1	3	1	3	1	3	1	3	1	3	1

Year of Production	2005		2006		2007		2008		2009		2010		2011		2012		2013	
DRAM ½ Pitch (nm) (contacted)	80		70		65		57		50		45		40		36		32	
Microprocessor	4	2	4	1.5	3.5	1.5	3	1	3	1	3	1	3	1	3	1	3	1
RF	5	3	4.5	2	4	1.5	4	1	4	1	4	1	4	1	4	1	4	1
Mixed-signal	4	2	3.5	2	3	1.5	3	1	3	1	3	1	3	1	3	1	3	1
Touchdowns Before Clean (Cantilever)	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline
Memory (DRAM)	400	20,000	400	20,000	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000
ASIC	3,250	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000
Microprocessor	1,250	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000
RF	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000
Mixed-signal	2,000	200,000	2,000	200,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000
Touchdowns Before Clean (Vertical)	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline
Memory (DRAM)	1,500	20,000	2,000	25,000	2,000	25,000	2,000	25,000	2,000	25,000	2,000	25,000	2,500	27,500	2,500	27,500	2,500	27,500
ASIC	1,500	17,500	2,000	20,000	2,000	20,000	2,000	20,000	2,000	20,000	2,000	20,000	2,500	22,500	2,500	22,500	2,500	22,500
Microprocessor	1,500	80,000	2,000	100,000	2,000	100,000	2,000	100,000	2,000	100,000	2,000	100,000	2,500	100,000	2,500	100,000	2,500	100,000
RF	100	20,000	100	25,000	100	25,000	125	25,000	125	25,000	125	25,000	125	27,500	125	27,500	125	27,500
Mixed-signal	1,500	85,000	2,000	87,500	2,000	87,500	2,000	87,500	2,000	87,500	2,000	87,500	2,500	90,000	2,500	90,000	2,500	90,000

Manufacturable solutions exist, and are being optimized 
Manufacturable solutions are known 
Interim solutions are known 
Manufacturable solutions are NOT known 

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Table 38b Wafer Probe Technology Requirements—Long-term Years *UPDATED*

Year of Production	2014		2015		2016		2017		2018		2019		2020	
DRAM ½ Pitch (nm) (contacted)	28		25		22		20		18		16		14	
I/O Pad Size (µm)	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y	X	Y
Wirebond	20	35	15	25	15	25	15	25	15	25	15	25	15	25
Bump	50	50	50	50	50	50	50	50	50	50	50	50	50	50
Scrub (% of I/O)	Offline	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH	AREA	DEPTH
Wirebond	20	40	20	40	20	40	20	40	20	40	20	40	20	40
Bump	30	30	30	30	30	30	30	30	30	30	30	30	30	30
<i>Multi-DUT Volume (% of Total Product Type Wafers Probed)</i>														
Memory (DRAM)	99.9		99.9		99.9		99.9		99.9		99.9		99.9	
ASIC	75		75		75		75		75		75		75	
Microprocessor	85		85		85		85		85		85		85	
RF	60		80		60		60		60		60		60	
Mixed-signal	80		80		80		80		80		80		80	
<i>Size of Probed Area (mm²)</i>														
Memory (DRAM)	100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer	
ADD Memory (FLASH)	100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer		100% of wafer	
ASIC	2400		2400		2400		2400		2400		2400		2400	
Microprocessor	2400		2400		2400		2400		2400		2400		2400	
RF	1225		1225		1225		1225		1225		1225		1225	
Mixed-signal	1600		1600		1600		1600		1600		1600		1600	
<i>Number of Probe Points /Touchdown</i>	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total	Signal	Total
Memory (DRAM)	20000	25000	20000	25000	20000	25000	20000	25000	20000	25000	20000	25000	20000	25000
ASIC	3000	9000	3000	9000	3000	9000	3000	9000	3000	9000	3000	9000	3000	9000
Microprocessor	2000	30000	2000	30000	2000	30000	2000	30000	30000	6000	30000	6000	30000	6000
RF	350	630	350	630	350	630	350	630	350	630	350	630	350	630
Mixed-signal	510	680	510	680	510	680	510	680	510	680	510	680	510	680
<i>Maximum Current (mA)</i>	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage	Probe Tip	DC Leakage
Memory (DRAM)	125	<10	125	<10	125	<10	125	<10	125	<10	125	<10	125	<10
ASIC	1000	<10	1000	<10	1000	<10	1000	<10	1000	<10	1000	<10	1000	<10
Microprocessor	1500	<10	1500	<10	1500	<10	1500	<10	1500	<10	1500	<10	1500	<10
RF	225	<10	225	<10	225	<10	225	<10	225	<10	225	<10	225	<10
Mixed-signal	275	<10	275	<10	275	<10	275	<10	275	<10	275	<10	275	<10
<i>Maximum Resistance (Ohm)</i>	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series	Contact	Series
Memory (DRAM)	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3
ASIC	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3	<0.5	<3
Microprocessor	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2	<0.5	<2

Year of Production	2014		2015		2016		2017		2018		2019		2020	
DRAM ½ Pitch (nm) (contacted)	28		25		22		20		18		16		14	
RF	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5
Mixed-signal	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5	<0.5	<1.5
Chuck Set-point (°C)	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.	Min.	Max.
Memory (DRAM)	-50	180	-50	180	-50	180	-50	180	-50	180	-50	180	-50	180
ASIC	-10	14	-10	14	-10	14	-10	14	-10	14	-10	14	-10	14
Microprocessor	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135	-30	135
RF	5	120	5	120	5	120	5	120	5	120	5	120	5	120
Mixed-signal	25	125	25	125	25	125	25	125	25	125	25	125	25	125
<i>Soak Time (minutes)</i>														
Memory (DRAM)	7		7		7		7		7		7		7	
ASIC	6		6		6		6		6		6		6	
Microprocessor	9		9		9		9		9		9		9	
RF	9		9		9		9		9		9		9	
Mixed-signal	9		9		9		9		9		9		9	
<i>Order Lead-time—Single DUT (weeks)</i>	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order
Memory (DRAM)	4	2	4	2	4	2	4	2	4	2	4	2	4	2
ASIC	2	1	2	1	2	1	2	1	2	1	2	1	2	1
Microprocessor	2	1	2	1	2	1	2	1	2	1	2	1	2	1
RF	3	1	3	1	3	1	3	1	3	1	3	1	3	1
Mixed-signal	2	1	2	1	2	1	2	1	2	1	2	1	2	1
<i>Order Lead-time—Multi-DUT (weeks)</i>	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order	1 st Order	Re-Order
Memory (DRAM)	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5	4.5	2.5
ASIC	3	1	3	1	3	1	3	1	3	1	3	1	3	1
Microprocessor	3	1	3	1	3	1	3	1	3	1	3	1	3	1
RF	4	1	4	1	4	1	4	1	4	1	4	1	4	1
Mixed-signal	3	1	3	1	3	1	3	1	3	1	3	1	3	1
<i>Touchdowns Before Clean (Cantilever)</i>	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline
Memory (DRAM)	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000	450	20,000
ASIC	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000	3,500	60,000
Microprocessor	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000	1,500	50,000
RF	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000	1,000	100,000
Mixed-signal	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000	2,000	300,000
<i>Touchdowns Before Clean (Vertical)</i>	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline	Online	Offline
Memory (DRAM)	2,500	27,500	2,500	27,500	2,500	27,500	2,500	27,500	2,500	27,500	2,500	27,500	2,500	27,500
ASIC	2,500	22,500	2,500	22,500	2,500	22,500	2,500	22,500	2,500	22,500	2,500	22,500	2,500	22,500

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Year of Production	2014		2015		2016		2017		2018		2019		2020	
DRAM ½ Pitch (nm) (contacted)	28		25		22		20		18		16		14	
Microprocessor	2,500	100,000	2,500	100,000	2,500	100,000	2,500	100,000	2,500	100,000	2,500	100,000	2,500	100,000
RF	125	27,500	125	27,500	125	27,500	125	27,500	125	27,500	125	27,500	125	27,500
Mixed-signal	2,500	90,000	2,500	90,000	2,500	90,000	2,500	90,000	2,500	90,000	2,500	90,000	2,500	90,000

Manufacturable solutions exist, and are being optimized

Manufacturable solutions are known

Interim solutions are known

Manufacturable solutions are NOT known

